

What is claimed is:

1. A reticle fabrication method comprising the steps of:

5 converting CAD (Computer Aided Design) data which is reticle design data to electron beam write data by means of a first data conversion device and to inspection data by means of a second data conversion device;

10 comparing said electron beam write data with said inspection data in a data verification device to verify whether or not there is a data conversion error;

fabricating a reticle using said electron beam write data after verifying that said electron beam write data is data correctly converted from said CAD data; and

15 inspecting a quality of said reticle based on said inspection data.

2. A reticle fabrication method comprising the steps of:

20 converting first electron beam write data for writing a figure pattern on a reticle based on reticle design data to second electron beam write data by means of a first data conversion device and to inspection data by means of a second data conversion device;

25 comparing said second electron beam write data with said inspection data in a data verification device to verify whether or not there is a data conversion error;

fabricating a reticle using said second electron beam write data after verifying that said second electron beam write data is data correctly converted from said first electron beam write data; and

5 inspecting a quality of said reticle based on said inspection data.

3. A reticle fabrication method comprising the steps of:

10 converting CAD (Computer Aided Design) data which is reticle design data to electron beam write data by means of a first data conversion device;

comparing said electron beam write data with said CAD data in a data verification device to verify whether or not there is a data conversion error;

15 fabricating a reticle using said electron beam write data after verifying that said electron beam write data is data correctly converted from said CAD data; and

20 inspecting a quality of said reticle based on inspection data acquired by performing data conversion of said electron beam write data by means of a second data conversion device.

4. A reticle fabrication method comprising the steps of:

25 converting CAD (Computer Aided Design) data which is reticle design data to first electron beam write data and

second electron beam write data by means of a first data conversion device and to first inspection data and second inspection data by means of a second data conversion device;

comparing said first electron beam write data with said
5 first inspection data in a first data verification device to verify whether or not there is a data conversion error;

comparing said second electron beam write data with said second inspection data in a second data verification device to verify whether or not there is a data conversion
10 error;

fabricating a reticle using said first and second electron beam write data after verifying that said first and second electron beam write data are data correctly converted from said CAD data; and

15 inspecting a quality of said reticle based on said first and second inspection data.

5. The reticle fabrication method according to claim 1, wherein said data verification device verifies whether or not there is a data conversion error by converting said
20 electron beam write data and said inspection data to raster images to be used by an electron beam writing device of a raster scan and stage continuous moving type and comparing said raster images with each other.

6. The reticle fabrication method according to claim
25 2, wherein said data verification device verifies whether or

not there is a data conversion error by converting said
electron beam write data and said inspection data to raster
images to be used by an electron beam writing device of a
raster scan and stage continuous moving type and comparing
5 said raster images with each other.

7. The reticle fabrication method according to claim
3, wherein said data verification device verifies whether or
not there is a data conversion error by converting said
electron beam write data and said inspection data to raster
10 images to be used by an electron beam writing device of a
raster scan and stage continuous moving type and comparing
said raster images with each other.

8. The reticle fabrication method according to claim
4, wherein said data verification device verifies whether or
15 not there is a data conversion error by converting said
electron beam write data and said inspection data to raster
images to be used by an electron beam writing device of a
raster scan and stage continuous moving type and comparing
said raster images with each other.

20 9. The reticle fabrication method according to claim
1, wherein said data verification device verifies whether or
not there is a data conversion error by converting said
electron beam write data and said inspection data to two-
dimensional coordinate data and comparing said two-
25 dimensional coordinate data with each other.

10. The reticle fabrication method according to claim
2, wherein said data verification device verifies whether or
not there is a data conversion error by converting said
electron beam write data and said inspection data to two-
5 dimensional coordinate data and comparing said two-
dimensional coordinate data with each other.

11. The reticle fabrication method according to claim
3, wherein said data verification device verifies whether or
not there is a data conversion error by converting said
10 electron beam write data and said inspection data to two-
dimensional coordinate data and comparing said two-
dimensional coordinate data with each other.

12. The reticle fabrication method according to claim
4, wherein said data verification device verifies whether or
15 not there is a data conversion error by converting said
electron beam write data and said inspection data to two-
dimensional coordinate data and comparing said two-
dimensional coordinate data with each other.